## Exploiting residual mechanical strain in CVD grown two-dimensional MoS<sub>2</sub> crystals

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Molybdenum disulphide (MoS<sub>2</sub>) is a layered Van der Waals solid enabling, as in the case of graphene, the isolation of a single  $MoS_2$  layer which is essentially a 2D-crystal. indirect-gap (1.3)Being an eV) semiconductor in its bulk form, MoS<sub>2</sub> attracted significant attention in the past years when it was found that its 2D counterpart is a direct-gap (~1.9 eV) material [1, 2]. Before this material can be properly incorporated into commercial devices. efficient large area growth methods are required.

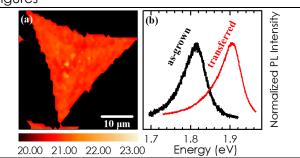
this work, a two-step atmospheric In pressure CVD method is presented, exhibiting controlled and large area growth of single and few-layered 2D-MoS<sub>2</sub> crystals through the reaction between sulphur vapours and pre-deposited sodium molybdate  $(Na_2MoO_4)$ Si/SiO<sub>2</sub> on а substrate. Depending on the precursor concentration the lateral size of the crystals can be controlled. Moreover, a monotonic increase of the substrate coverage with the precursor concentration is established, which enables the preparation of either monolayers isolated homogeneously distributed on the substrate or continuous single and few-layer MoS<sub>2</sub> films with photoelectron domains. X-ray spectroscopy was used to verify the

stoichiometry of the produced crystals, Transmission Electron Microscopy while confirmed the high quality of the crystals. Raman and Photoluminescence (PL) spectroscopies are employed to thoroughly study the fabricated crystals before and after transferring them onto a polymer substrate. Significant spectral variations between the as-grown and transferred crystals were found. An optical analysis [3] was conducted, identifying mechanical strain as the main source of the spectral variations. It was found that strain relaxation takes place due to the transferring of the 2D-crystal. The magnitude of the residual strain imparted on the as-grown crystals which can be as large as 0.5%- is adequate to shift the direct transition of MoS<sub>2</sub> by almost 80 meV. The large residual strain experienced by the as-grown crystals enabled an estimation of the deformation potential of the direct optical transition of MoS<sub>2</sub>.

## References

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## Figures



**Figure 1**: (a) Raman image of the  $\Delta\omega$  value of an as grown-CVD MoS<sub>2</sub> monolayer on Si-SiO<sub>2</sub> substrate. The average  $\Delta\omega$  value is 20.7 cm<sup>-1</sup>. (b) PL spectra of as grown and transferred crystal. The PL peak in this case is shifted roughly by 100 meV.

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